



Docket No. 008066 USA/MTCG/PCTRL

PATENT/OFFICIAL
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AUG 11 2005 IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Patent Application of

Susie Xiuru YANG et al.

Serial No. 10/809,908 : Group Art Unit: 2812

Filed: March 26, 2004 : Examiner:

For: IMPROVED CONTROL OF METAL RESISTANCE IN SEMICONDUCTOR
PRODUCTS VIA INTEGRATED METROLOGY

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

In accordance with 37 C.F.R. § 1.97(g) and (h), the filing of this IDS should not be construed as a representation that a search had been made or that information cited is, or is considered to be, material to patentability as defined in 37 C.F.R. § 1.56 (b), or that any cited document listed or attached is (or constitutes) prior art. Unless otherwise indicated, the date of

publication indicated for an item is taken from the face of the item, and Applicant reserves the right to prove that the date of publication is in fact different.

No fee is believed to be required; however, the Commissioner is authorized to charge any deficiency in any fees pursuant to 37 CFR § 1.17 associated with this communication and to credit any excess payment to Deposit Account No. 08-0219.

Respectfully submitted,

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INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)			ATTY. DOCKET NO. 008066 USA/ MTCG/PCTRL	SERIAL NO. 10/809,908		
			APPLICANT Susie Xiuru YANG et al.			
			FILING DATE March 26, 2004	GROUP 2812		
U.S. PATENT DOCUMENTS						
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)						
	Boning, Duane et al. "Run by Run Control of Chemical-Mechanical Polishing." <i>IEEE Trans.</i> October 1996. Vol. 19, No. 4. pp. 307-314.					
	Moyné, James et al. "A Run-to-Run Control Framework for VLSI Manufacturing." <i>Microelectronic Processing '93 Conference Proceedings</i> . September 1993.					
	Telfeyan, Roland et al. "Demonstration of a Process-Independent Run-to-Run Controller." <i>187th Meeting of the Electrochemical Society</i> . May 1995.					
	Moyné, James et al. "A Process-Independent Run-to-Run Controller and Its Application to Chemical-Mechanical Planarization." <i>SEMI/IEEE Adv. Semiconductor Manufacturing Conference</i> . August 15, 1995.					
	Moyné, James et al. "Adaptive Extensions to be a Multi-Branch Run-to-Run Controller for Plasma Etching." <i>Journal of Vacuum Science and Technology</i> . 1995.					
	Sachs, Emanuel et al. "Process Control System for VLSI Fabrication."					
	Chaudhry, Nauman et al. "Active Controller: Utilizing Active Databases for Implementing Multi-Step Control of Semiconductor Manufacturing." <i>University of Michigan</i> . pp. 1 - 24.					
	Chaudhry, Nauman et al. "Designing Databases with Fuzzy Data and Rules for Application to Discrete Control." <i>University of Michigan</i> . pp. 1 - 21.					
	Chaudhry, Nauman A. et al. "A Design Methodology for Databases with Uncertain Data." <i>University of Michigan</i> . pp. 1 - 14.					
	Khan, Kareemullah et al. "Run-to-Run Control of ITO Deposition Process." <i>University of Michigan</i> . pp. 1 - 6.					
	Moyné, James et al. "Yield Improvement @ Contact Through Run-to-Run Control."					
	Kim, Jiyoun et al. "Gradient and Radial Uniformity Control of a CMP Process Utilizing a Pre- and Post-Measurement Strategy." <i>University of Michigan</i> .					
EXAMINER	DATE CONSIDERED					

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.